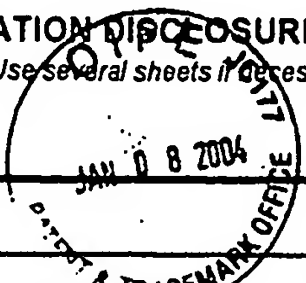


INFORMATION DISCLOSURE CITATION
(Use several sheets if necessary)



ATTY DOCKET NO.
YOR920030013US1

SERIAL NO.
10/680,260

APPLICANT(S)
David Abraham et al.

FILING DATE
October 8, 2003

GROUP
Not Yet Assigned

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
A.M	6,440,520	08/27/02	Baglin et al.			
I	6,331,364	12/18/01	Baglin et al.			
I	6,383,597	05/07/02	Fullerton et al.			

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

A.M		Bruenger et al., "Ion projection lithography for resistless patterning of thin magnetic films", 25th International Conference on Micro and Nano Engineering, Rome Italy, 21-23 September 1999 and Microelectron. Eng. (Netherlands), Vol. 53, No. 1-4, June 2000, Pages 605-608.
A.M		Eugene Chen, et al., "Magnetic tunnel junction pattern technique", Silicon Magnetic Systems, Cypress Semiconductor, San Jose, CA, Journal of Applies Physics, Volume 93, Number 10, May 15, 2003, p. 8379.

EXAMINER

DATE CONSIDERED

ANH D. MAI

5/16/05

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION
(Use several sheets if necessary)

ATTY DOCKET NO.

YOR920030013US1

SERIAL NO.

10/680,260

APPLICANT(S)

David Abraham et al.

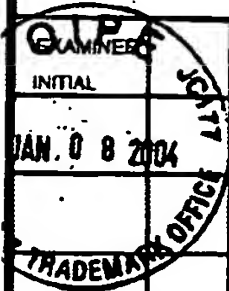
FILING DATE

October 8, 2003

GROUP

Not Yet Assigned

U.S. PATENT DOCUMENTS



DOCUMENT NUMBER

DATE

NAME

CLASS

SUBCLASS

FILING DATE
IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER

DATE

COUNTRY

CLASS

SUBCLASS

TRANSLATION

YES

NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

B.D. Terris et al., "Patterning magnetic films by ion beam irradiation", J. Appl. Phys., (USA), Vol. 87, No. 9, Pt. 1-3, May 1, 2000, pp.7004-6.

Corporate Associates, "Physics Helps Redesign Dow Chemical," 39 The Industrial Physicist, April 1999, American Institute of Physics, page 1.

EXAMINER

ANH D. MAI

DATE CONSIDERED

5/16/05

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.